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## U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
ju	5,674,355	10/1997	Cohen et al.	156	652.1	

## FOREIGN PATENT DOCUMENTS

Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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ju	Wu, P.K., "XPS Study of Buried Metal/Polymer and Polymer/Metal Interface", <i>Mat. Res. Soc. Symp. Proc.</i> Vol. 385 (1995), pp. 79-90.
ju	Clark, D.T. et al., "Surface Modification by Plasma Techniques. I. The Interactions of a Hydrogen Plasma with Fluoropolymer Surfaces", <i>Journal of Polymer Science: Part A: Polymer Chemistry</i> , Vol. 25, 2643-64 (1987).
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Examiner		Date Considered	11/17/03
*Examiner:	Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		
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